



CORWIL
TECHNOLOGY CORPORATION

Die Prep Considerations for IC Device Applications

CORWIL Technology
1635 McCarthy Blvd
Milpitas, CA 95035

Jonny Corrao

Die Prep

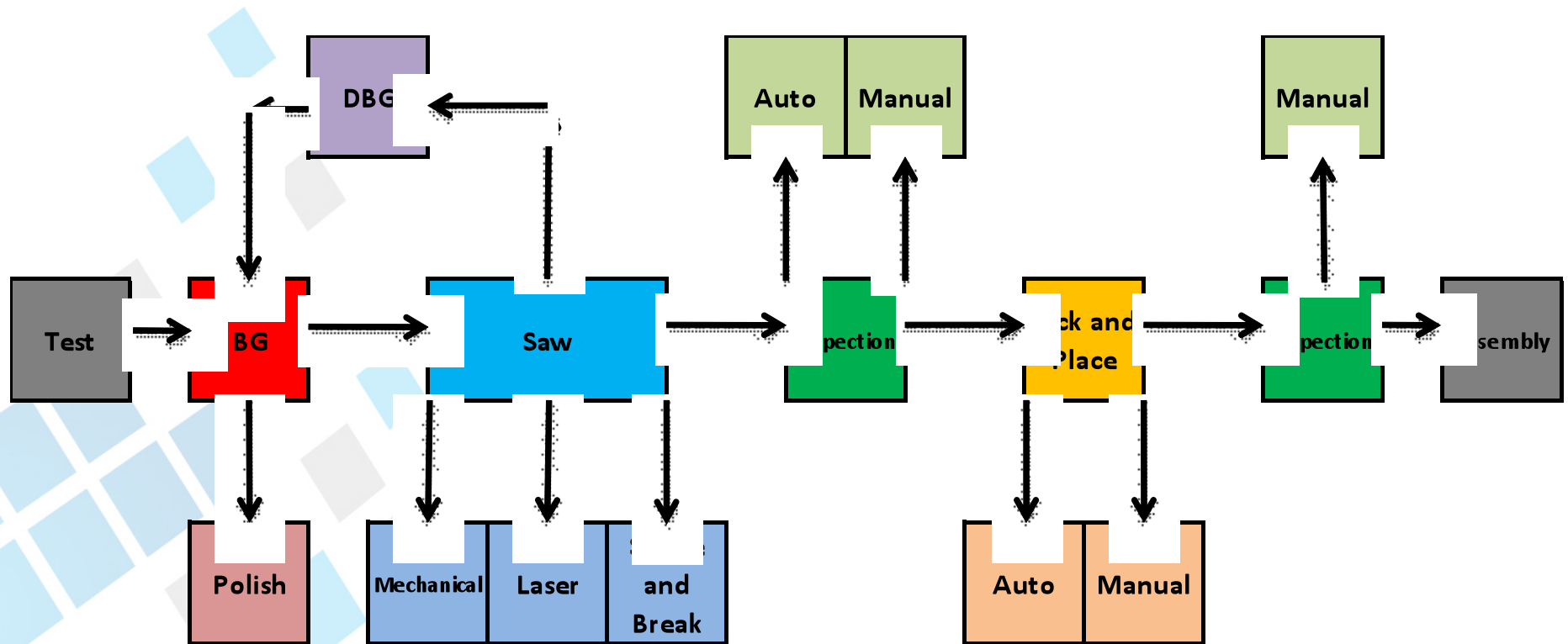
While quality, functional parts are the end goal for all semiconductor companies, getting from the fab to the assembly line is often an undervalued aspect of the IC supply chain.

Wafer design and characteristics are critical for not only the final product, but also for optimizing an efficient and cost-effective production stream. Utilizing specific process methods can improve die quality and reduce unexpected downstream hiccups.

In this presentation we will explore the various means of die preparation and what you should look for when designing your wafers to enhance the probability of success during die prep.

Die Prep

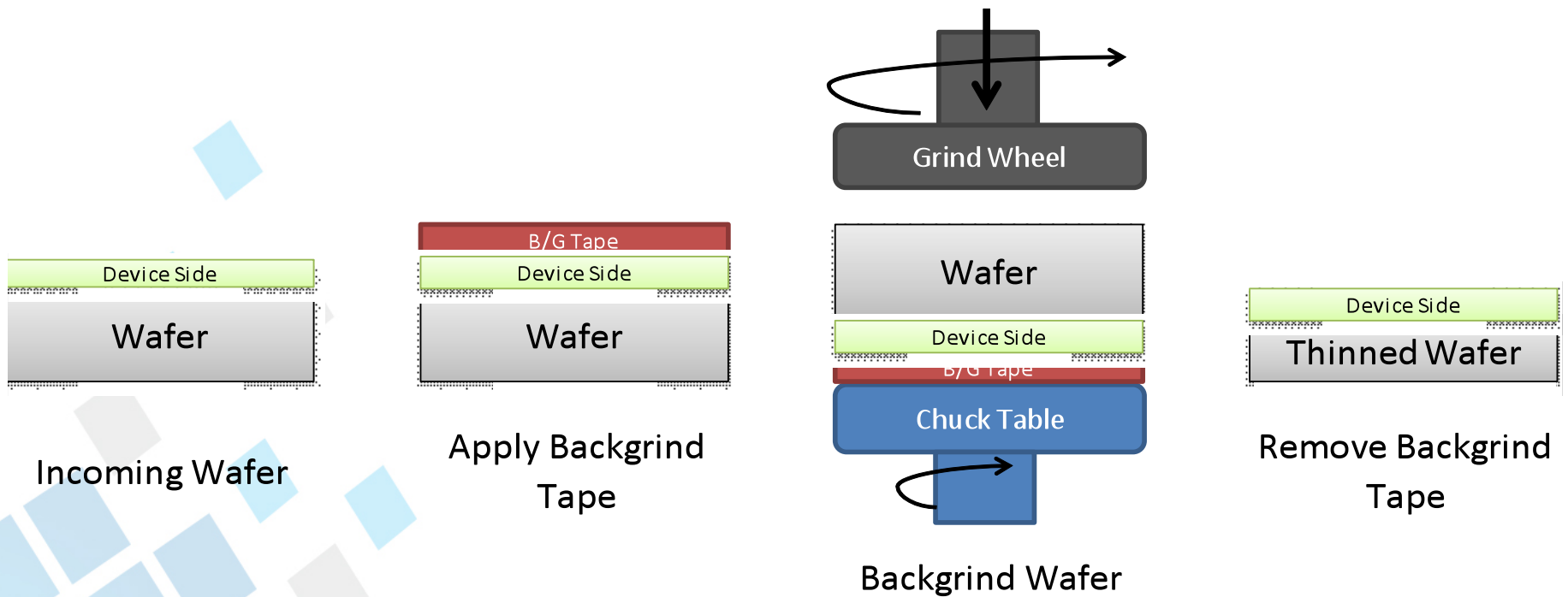
- Die prep encompasses all processes that take an IC from a wafer after test and into die form prior to assembly



Wafer Thinning

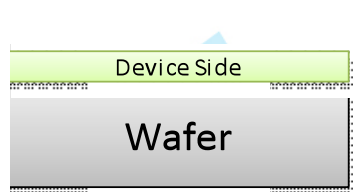
- Wafer thinning is the process of removing material from the backside of a wafer to a desired final target thickness
- The most common methods of wafer thinning are mechanical grind, wet etch, and chemical-mechanical planarization (CMP)
- A protective film is typically applied on the device side of the wafer to secure the die during thinning
- Die strength and smoothness can be increased based on grit/slurry selection, while also decreasing warpage and subsurface damage

Wafer Thinning

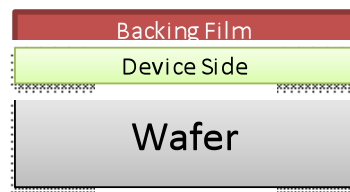


Mechanical Grinding

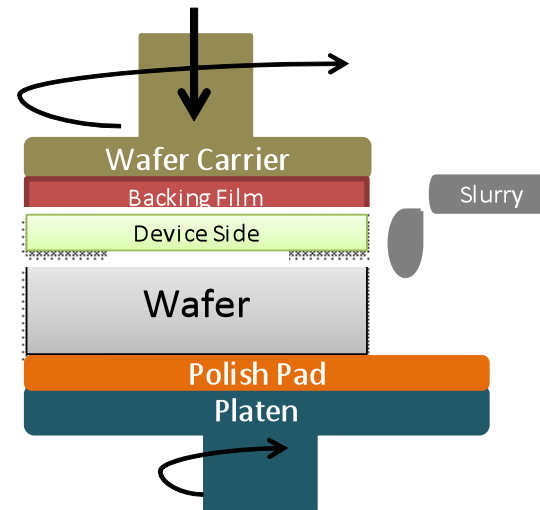
Wafer Thinning



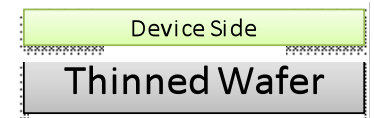
Incoming Wafer



Backing Film Application



Polish Wafer



Remove Backing Film

CMP

Wafer Thinning

Mechanical Grind

- Lower cost
- Clean process
- Faster throughput

- Higher roughness
- Ultra-thin wafer handling

Benefits

- Lower roughness
- Tighter TTV
- More forgiving when processing hard and exotic materials

Challenges

- Dirty process
- Consumable disposal
- Cost of ownership

CMP

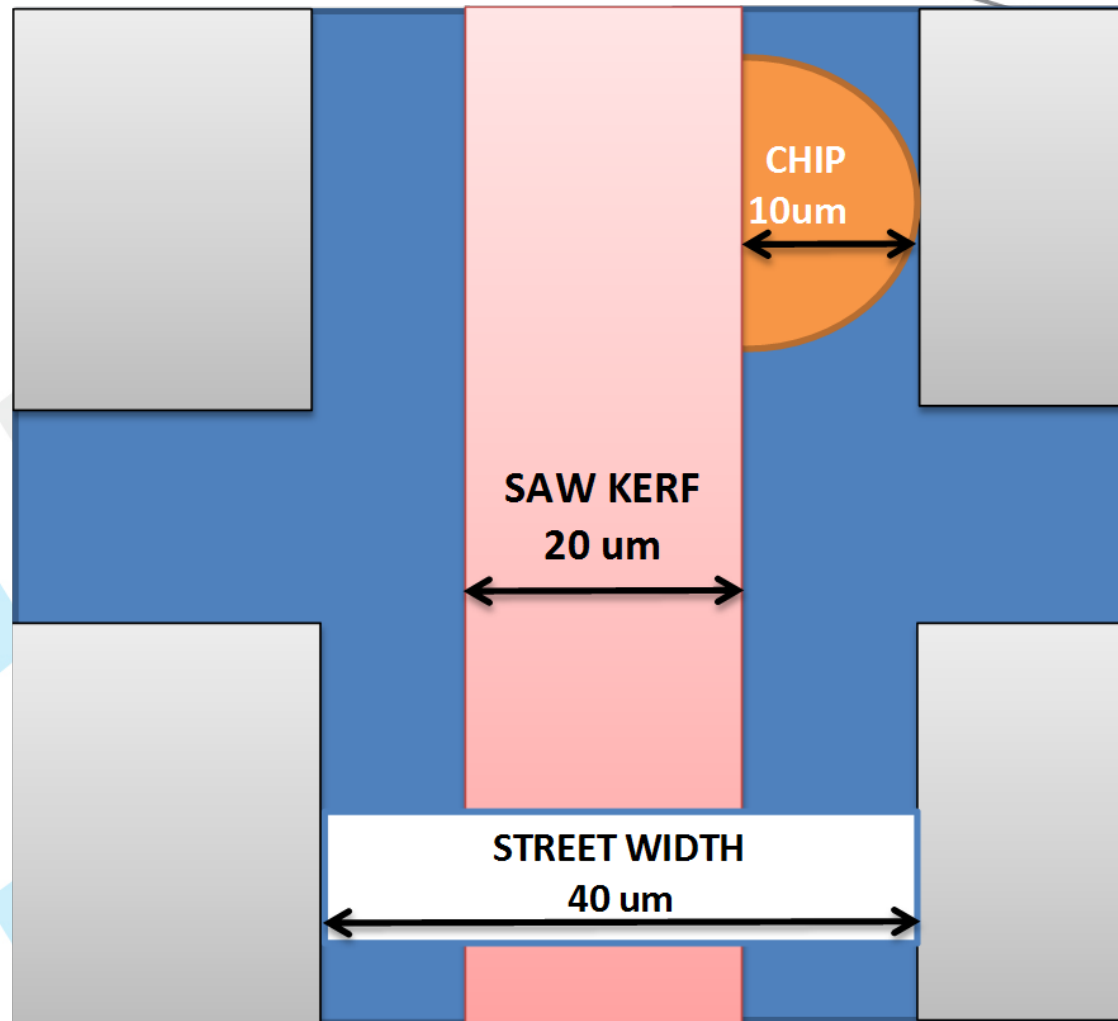
Wafer Singulation

- Singulation is the process of isolating individual IC's from a wafer
- The most common methods of wafer singulation are mechanical dicing, laser dicing, scribe and break, and dice before grind (DBG)
- Wafers are typically mounted to tape and frame when singulated
- Material type, wafer thickness, and street width are the most critical factors in wafer singulation when determining the optimal process method

Mechanical Dicing

- Mechanical blade dicing is the traditional method of singulating die utilizing (typically) a diamond embedded blade to remove material while process water cools the blade and workpiece
- While more robust and flexible than other methods, mechanical dicing does produce a large kerf and chipping is inherent with the process
- Consumable costs are prevalent due to blade wear and replacement
- Mechanical dicing is limited by street width

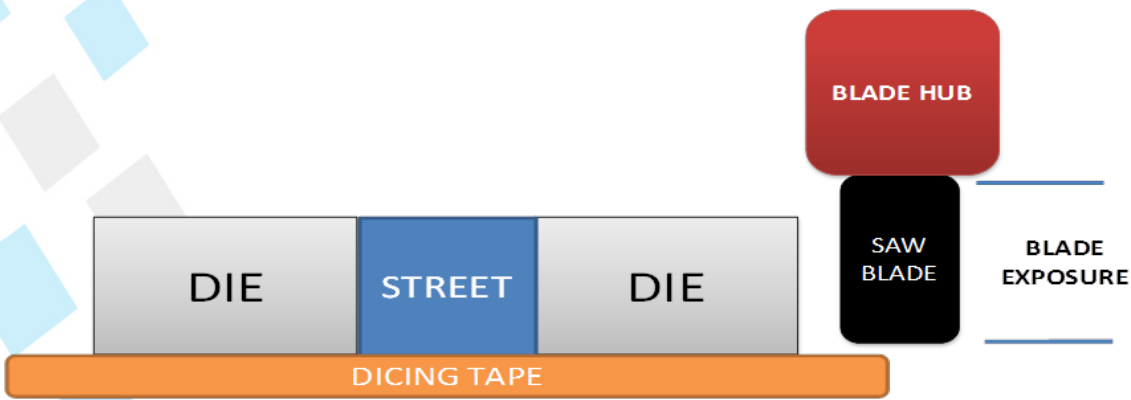
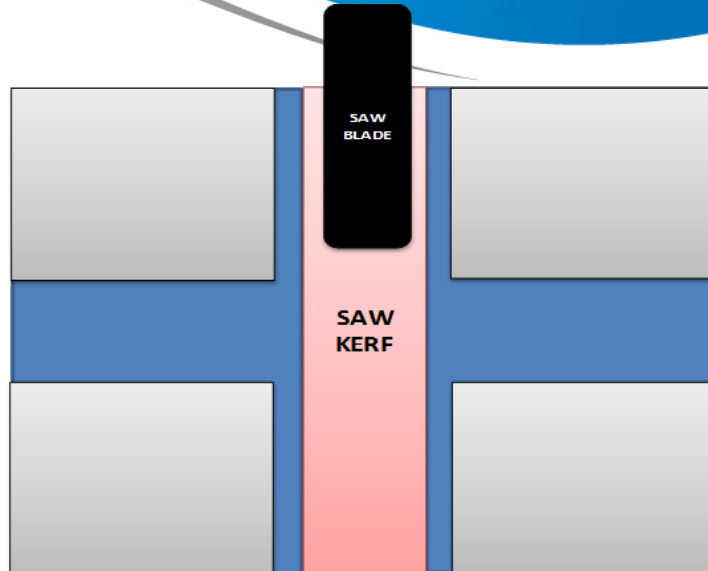
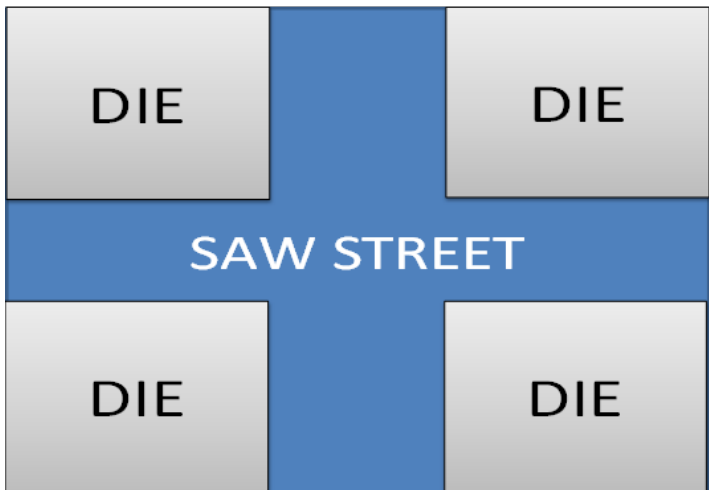
Mechanical Dicing



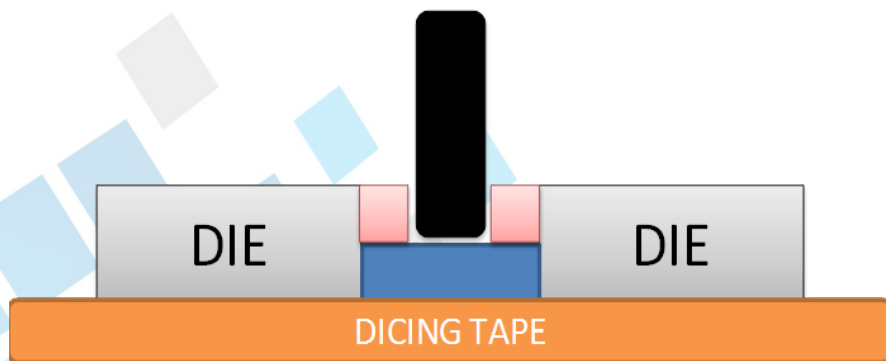
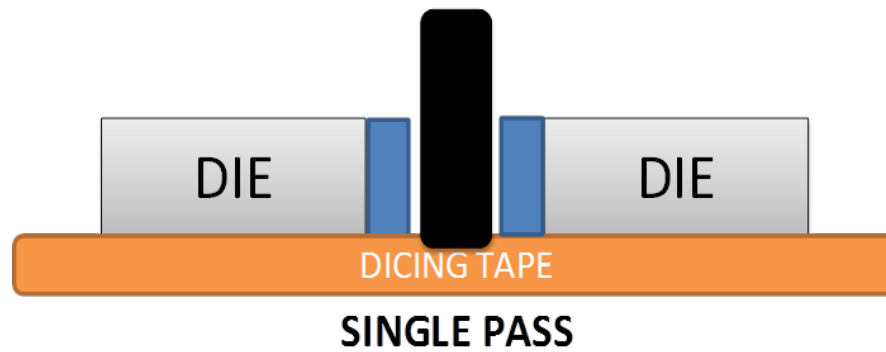
Mechanical Dicing

- Street width governs the blade/kerf width
- Total thickness (including bumps) determines blade exposure
- Blade exposure is restricted by blade width
- The narrower the blade the smaller the exposure
- Therefore, for wafers with narrow streets thinning is required

Mechanical Dicing



Mechanical Dicing



Mechanical Dicing

Single Pass

- Faster throughput
- Ultra-thin wafer dicing
- Narrow streets

Benefits

- Street width to thickness ratio
- Cut quality

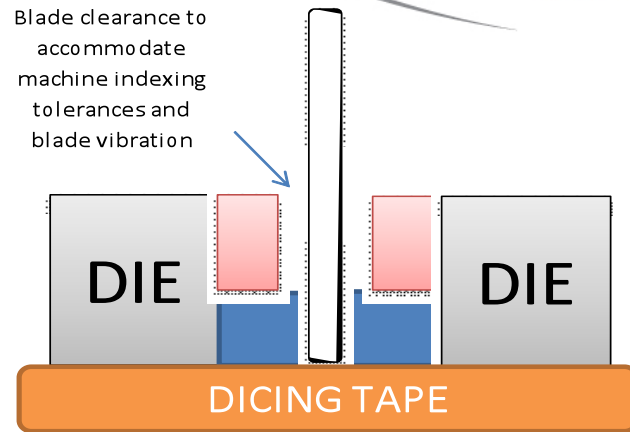
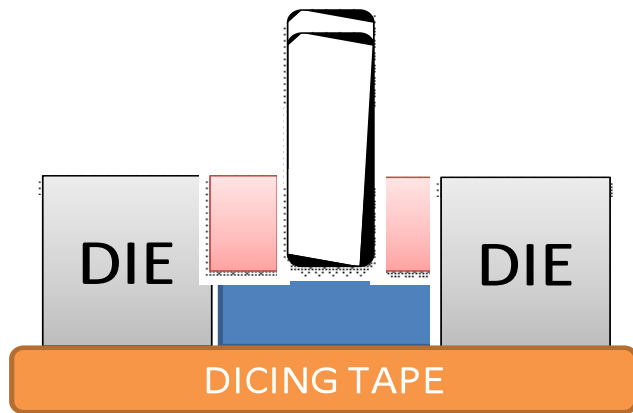
Challenges

Step Cut

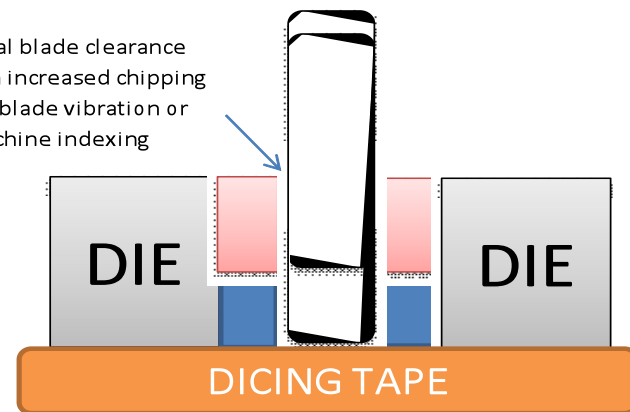
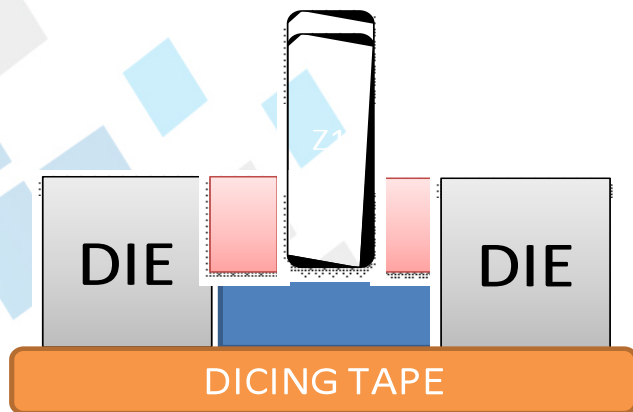
- Improved topside and backside quality
- Thick wafers

- Slower throughput
- Increased inventory and consumables

Mechanical Dicing

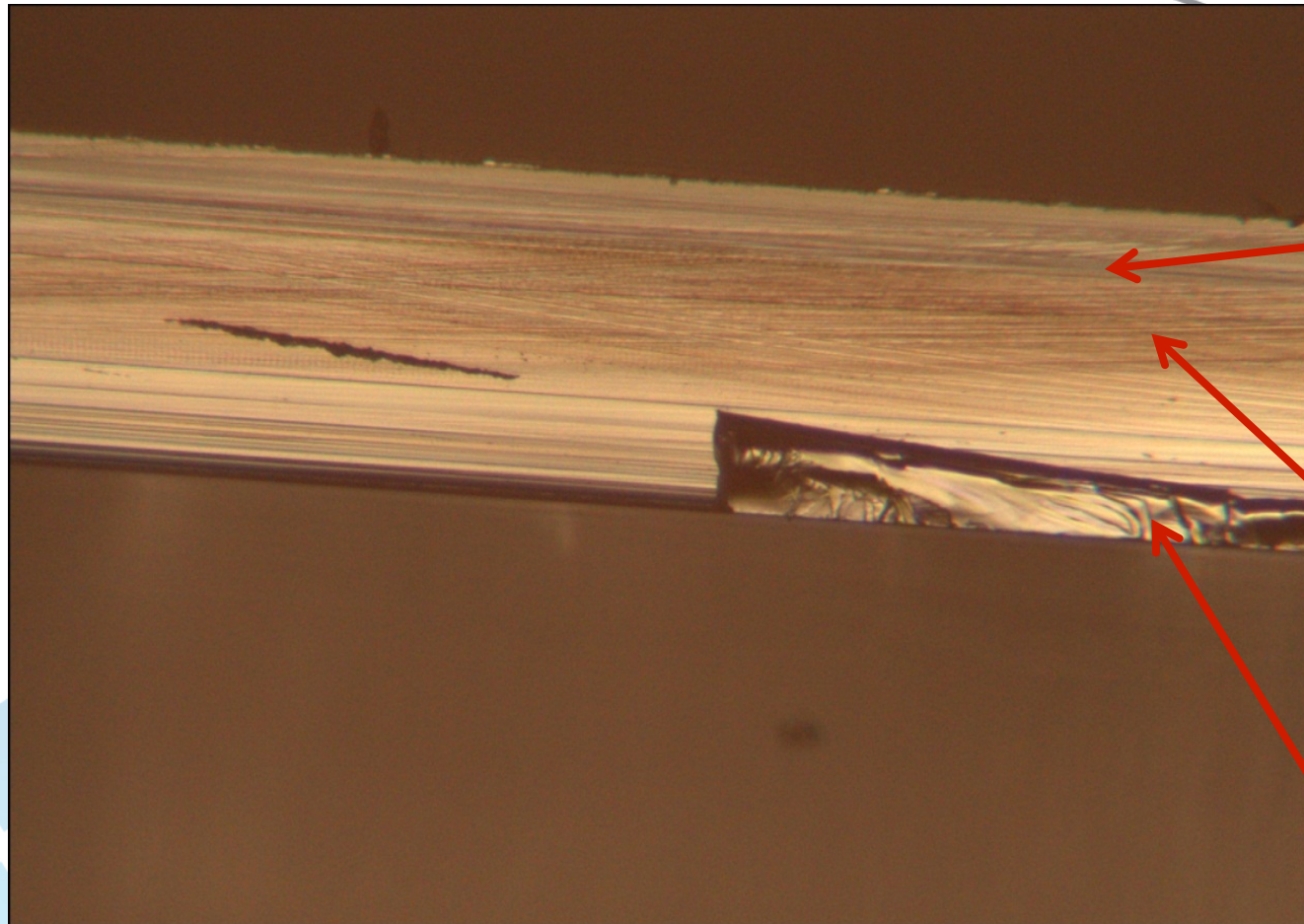


Step Cut - Wider Z1 Blade



Step Cut - Same Blade Width

Mechanical Dicing



Cut line difficult to distinguish due to same blade width on Z1 and Z2

Dark discoloration and burn mark from blade rubbing and glazing. Blade marks against blade rotation

Backside chipping created from blade vibration and minimal clearance

Step Cut Defects – Same Blade Width

Mechanical Dicing



Definitive cut line

No sign of blade rubbing or burning

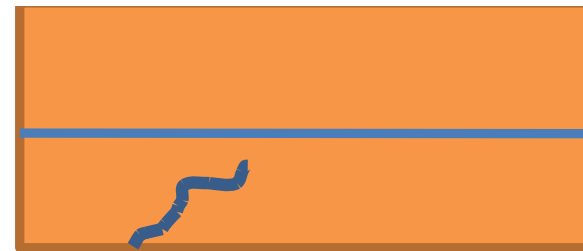
Clean blade marks going with blade rotation

Step Cut – Differing Blade Widths

Mechanical Dicing



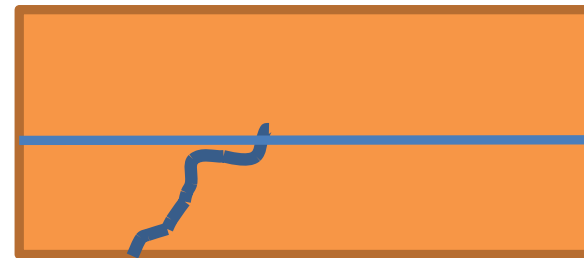
Location of sidewall crack subjective, potentially rejected



Sidewall "guard ring" clearly identifies crack as acceptable per 50% sidewall spec



Location of sidewall crack subjective, potentially accepted

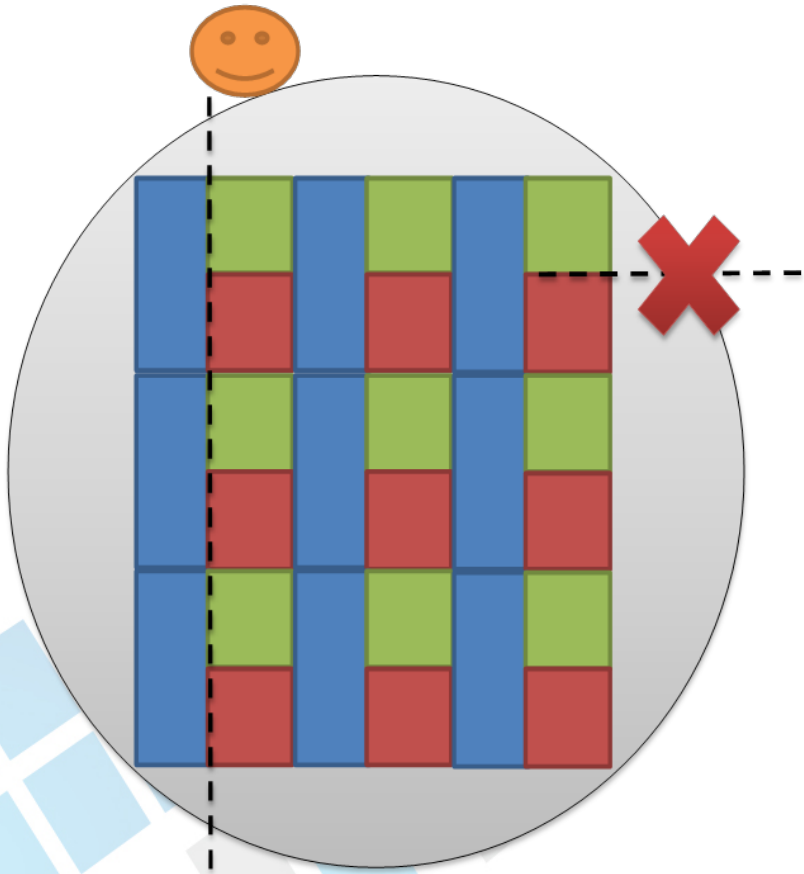


Sidewall "guard ring" clearly identifies crack as a reject per 50% sidewall spec

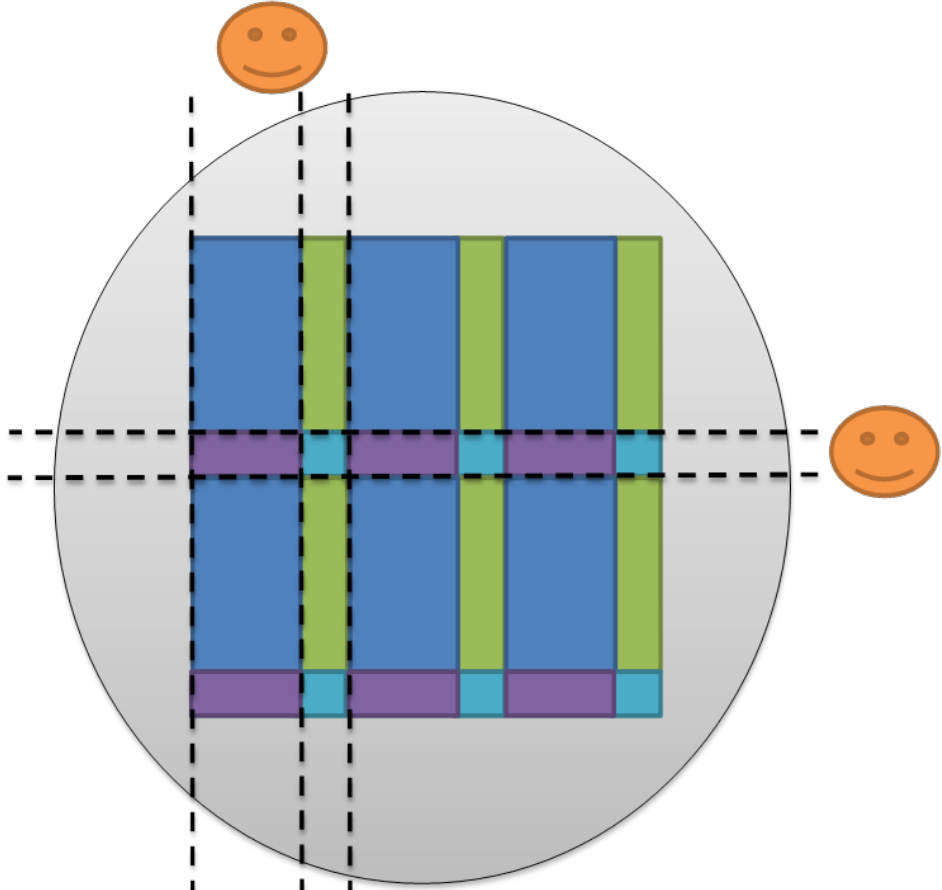
MPW Dicing

- Multi-project wafers require the indexing to be consistent across all die in a reticle in order to singulate without sacrificing die
- Inconsistent indexing between die in a reticle would require die to be sacrificed, or cut through, in order to salvage the target die
- If all die in an inconsistent reticle are required to be saved, then remounting is necessary

MPW Dicing



REMOUNT REQUIRED

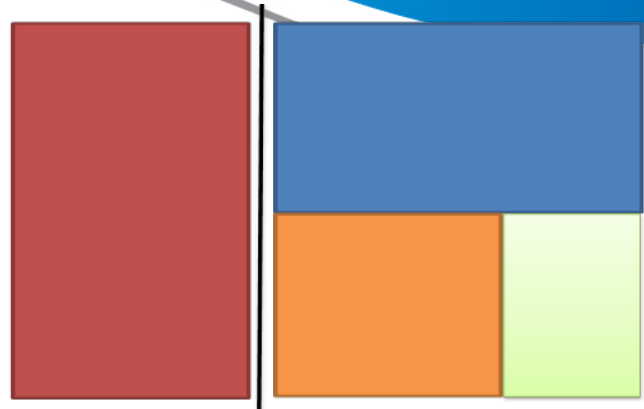


MULTI-INDEXING (NO REMOUNT REQUIRED)

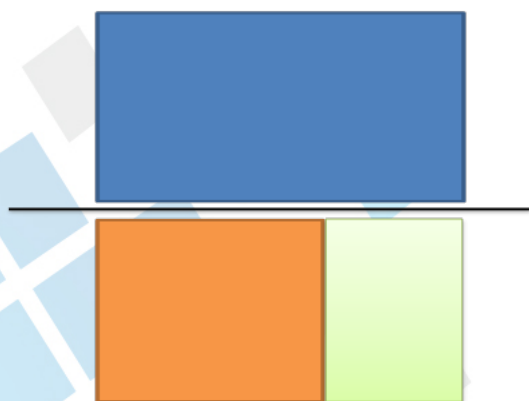
MPW Dicing



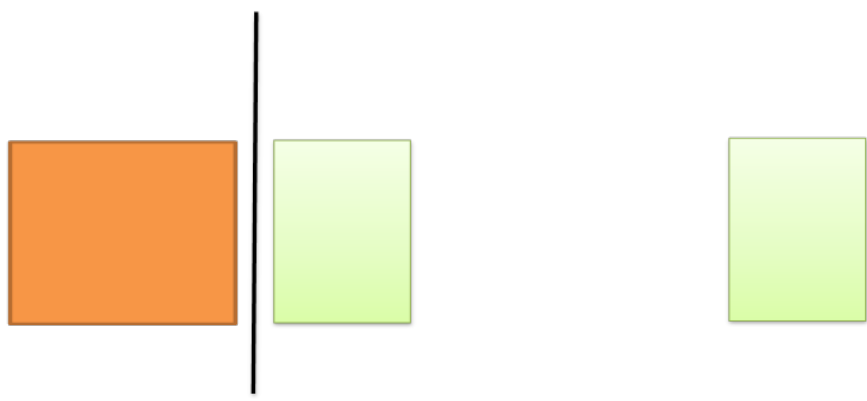
RETICLE LAYOUT



(1) MOUNT RETICLE (2) PERFORM CUT TO ISOLATE LARGE RED DIE



(3) REMOVE RED DIE FROM DICING TAPE. (4) REMOVE RETICLE. (5) REMOUNT RETICLE. (6) PERFORM CUT TO ISOLATE BLUE DIE



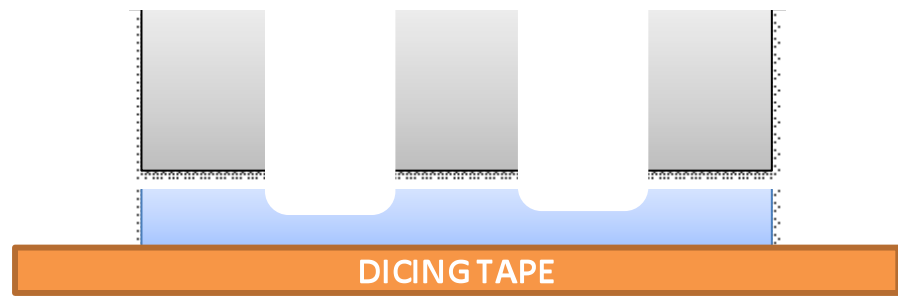
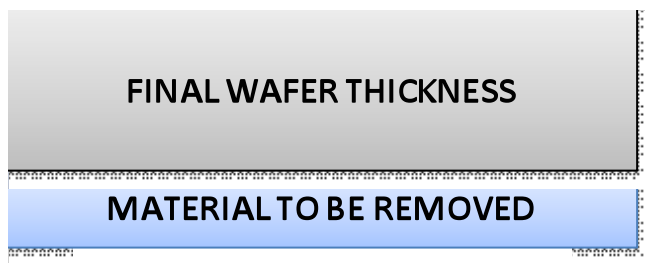
(7) REMOVE BLUE DIE. (8) REMOVE RETICLE. (9) REMOUNT RETICLE. (10) PERFORM CUT TO ISOLATE ORANGE DIE.

(11) REMOVE ORANGE DIE. (12) PLATE DESIRED YELLOW DIE

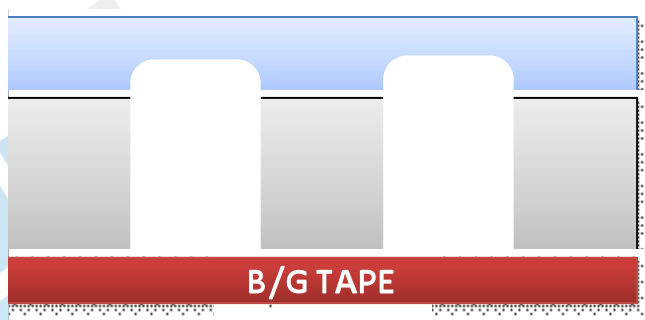
Dice Before Grind

- Dice Before Grind (DBG) is a process in which the wafers are trenched prior to backgrind and then thinned to singulate the die
- The DBG process utilizes the same consumables and equipment as mechanical thinning and dicing with the only change being the order in which they are performed
- DBG minimizes backside chipping
- Wafers must be thinned to utilize DBG and the process is limited by the wafer thickness and die size

Dice Before Grind



Trench beyond final target thickness



Mounted singulated die to dicing tape and frame and remove B/G tape

Thin wafer to target

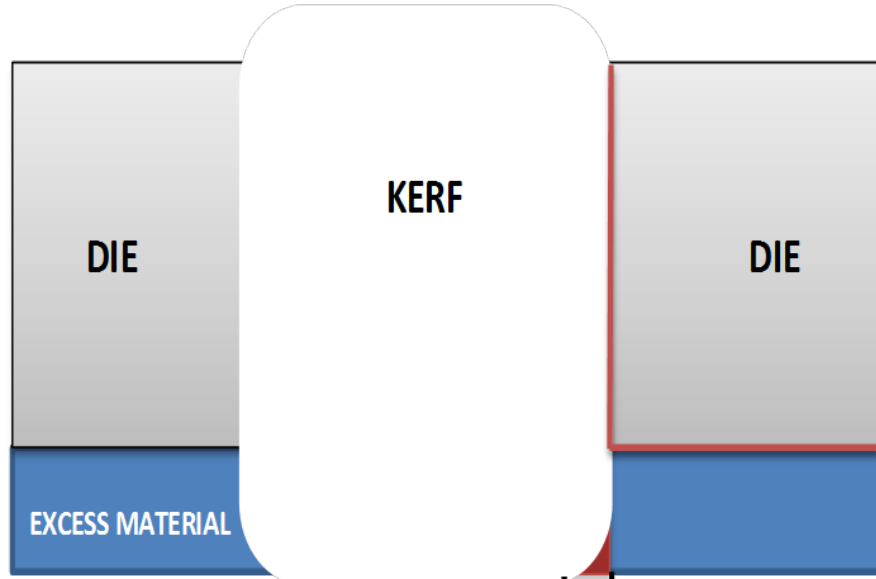
Dice Before Grind

CONVENTIONAL DICING



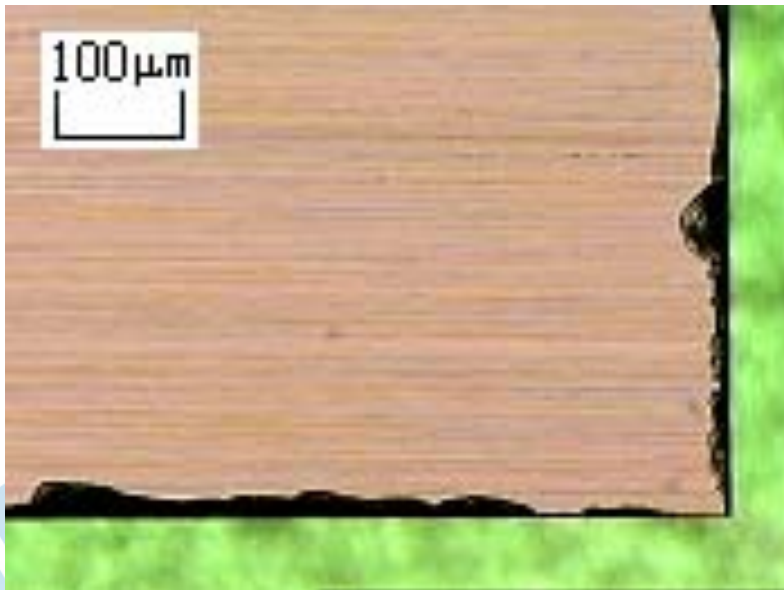
Backside "toe" from curvature of the blade remaining on die

DBG



Backside "toe" removed during grind leaving clean die edge

Dice Before Grind



Single Pass

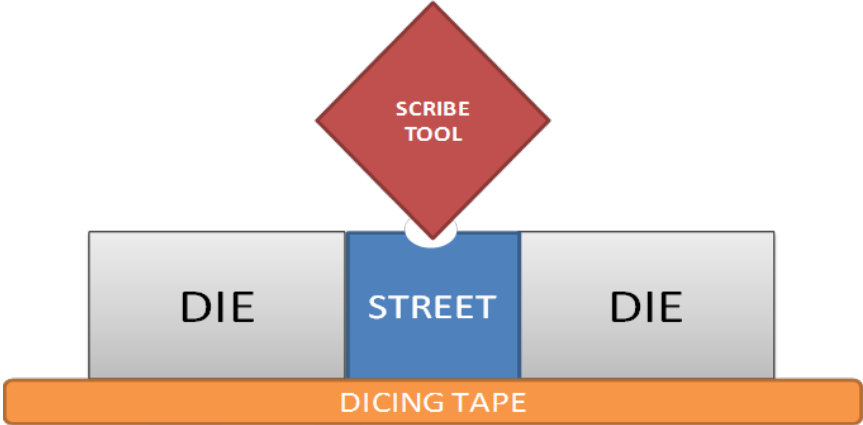


DBG

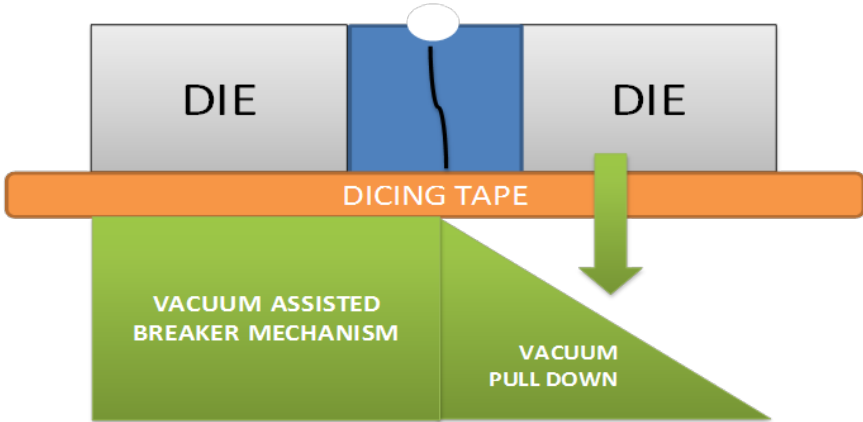
Scribe and Break

- Scribe and Break is the process of depressing material into the saw street to create stress in the wafer and then fracturing the wafer along that stress line
- SnB is a completely dry process involving no liquids or chemicals and there is no material loss during the process
- SnB is ideal for ultra-thin silicon, hard materials (glass), and fragile material (GaAs, InP)
- Wafer thickness, die size, and crystalline orientation are limiters for the SnB process

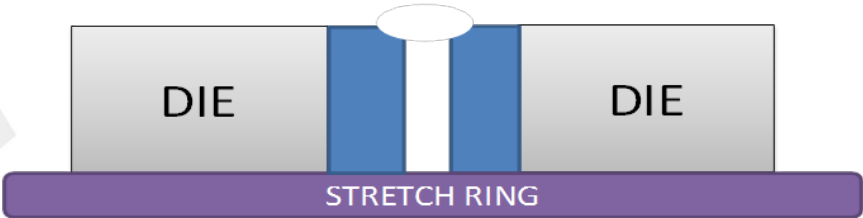
Scribe and Break



SCRIBE WAFER ON DICING TAPE AND FILM FRAME

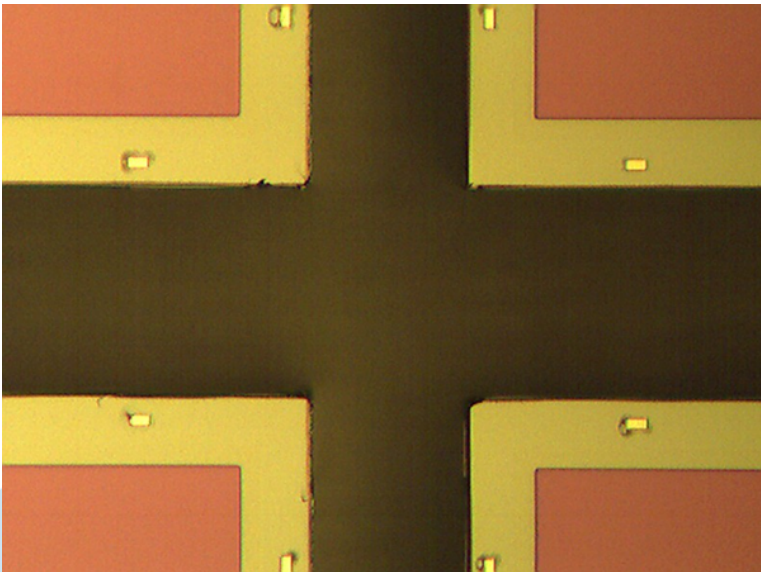


DIE BREAK PERFORMED BY "BENDING" WAFER WITH STRESS LINE CENTERED ON THE BREAKER BAR EDGE

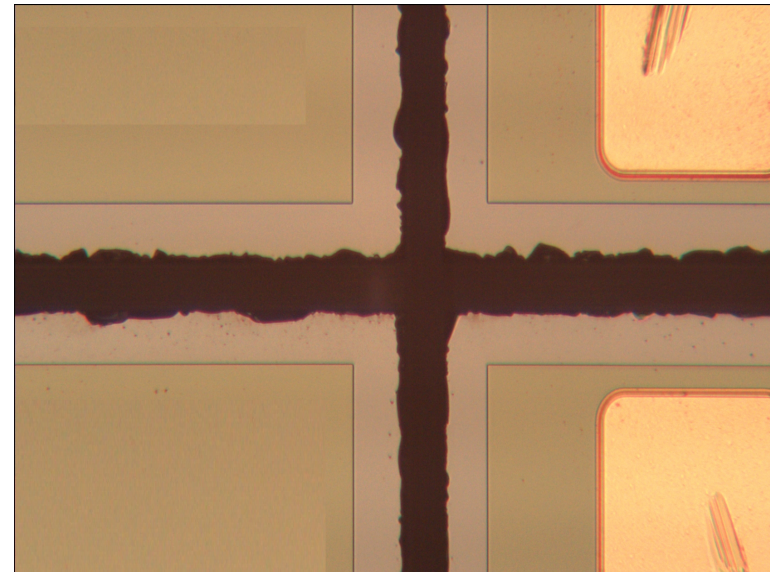


TRANSFER TO STRETCH RING FOR INCREASED DIE SEPARATION

Scribe and Break



GaAs Scribe and Break

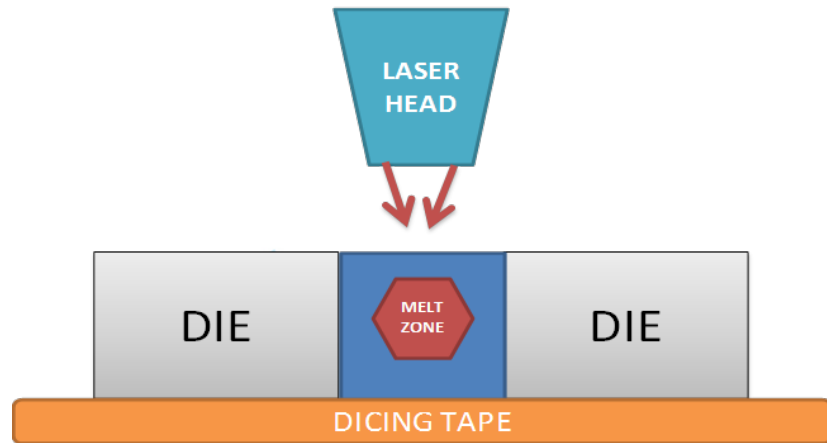


GaAs Mechanical Dicing

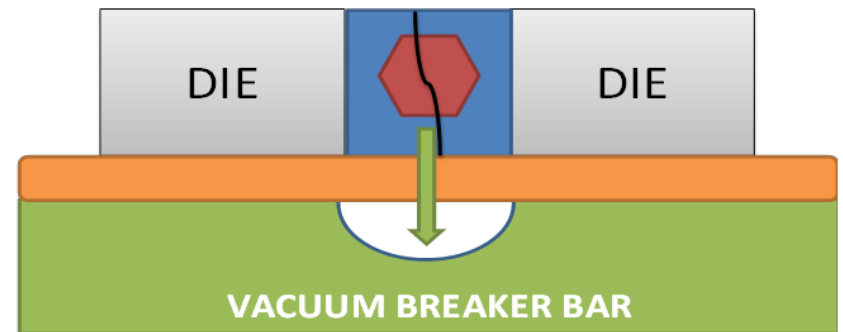
Stealth Dicing

- Stealth Dicing is essentially a scribe and break process where the scriber is a laser instead of a diamond
- The laser generates a melt zone in the middle of the saw street creating a stress line in the wafer. The stress line is then broken and the die are separated
- Stealth dicing is ideal for wafers that have extremely narrow streets or non-contact products such as MEMS devices
- The heat generated from the laser can have adverse effects on die performance

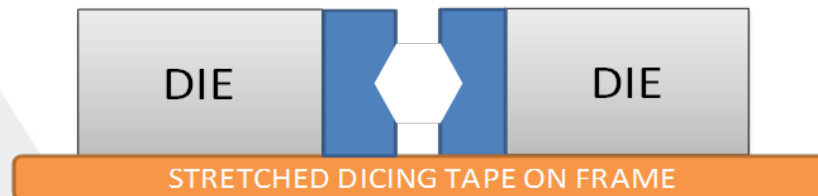
Stealth Dicing



LASER SCRIBE GENERATING MELT ZONE IN MIDDLE OF THE STREET

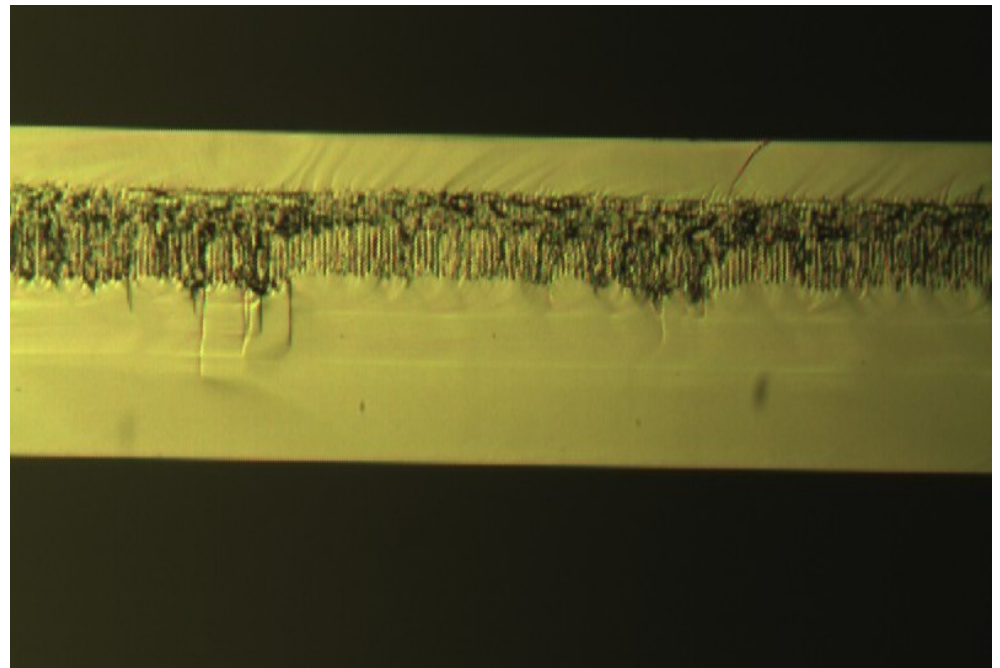
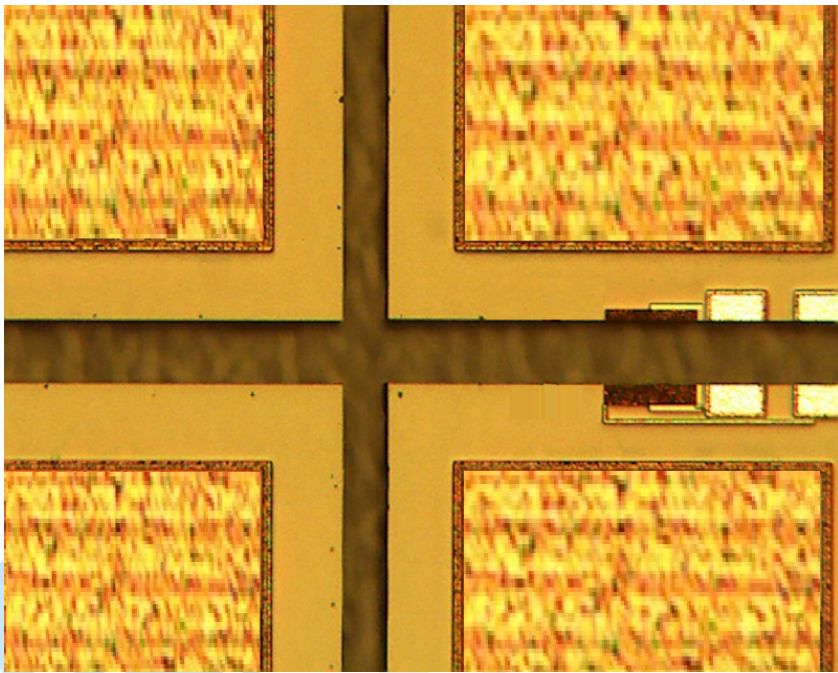


BREAKER BAR PULLS VACUUM ON THE STREET CAUSING THE MELT ZONE AND STREET TO FRACTURE



THE DICING TAPE IS STRETCHED ONTO A FILM FRAME TO PROVIDE INCREASED DIE SEPARATION

Stealth Dicing

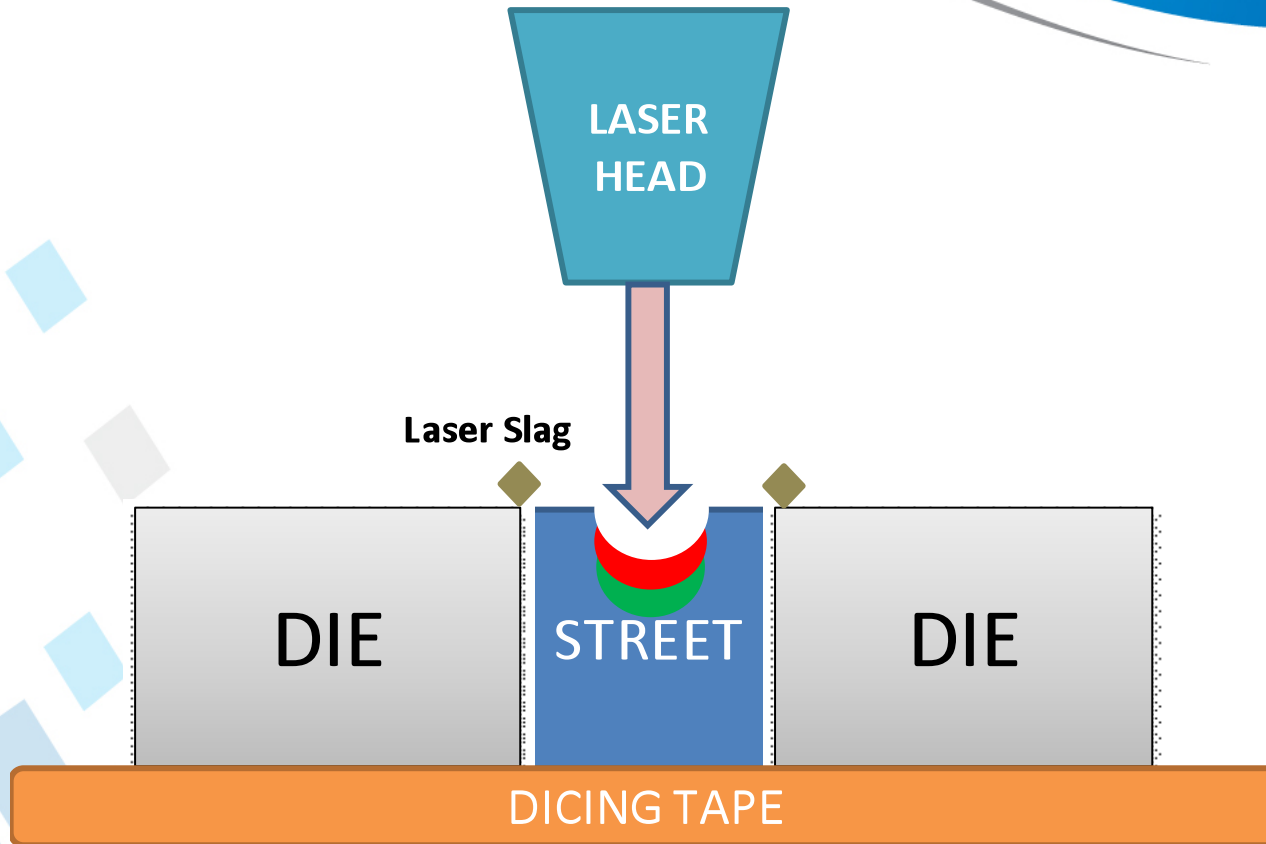


Stealth Dicing Topside and Melt Zone

Laser Ablation

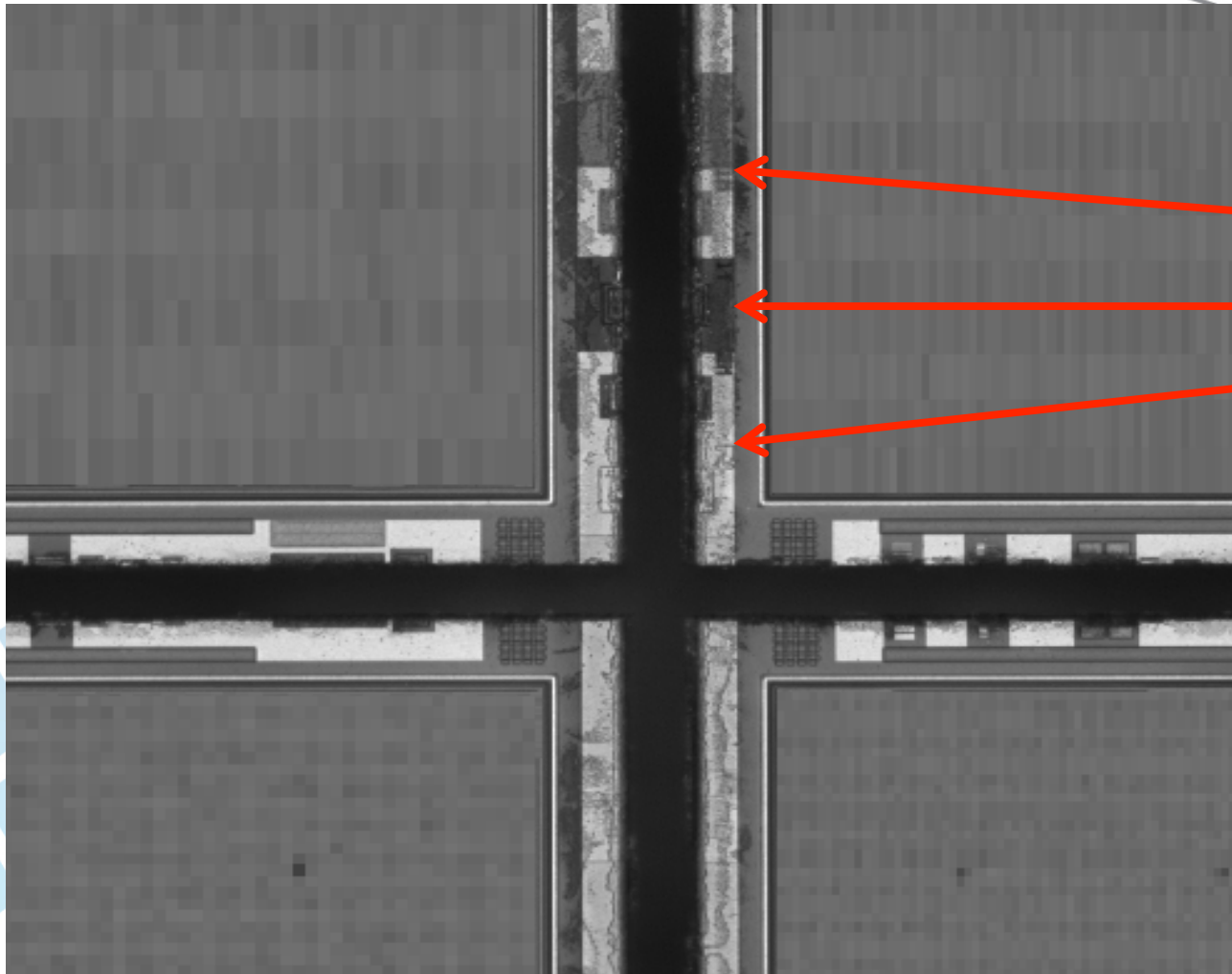
- Laser ablation dicing is the process of removing material in the wafer street with a laser to singulate the die
- Laser ablation is ideal for thin wafers with narrow streets
- However, laser ablation generates molten debris, or slag, that can get on the die surface and is difficult to remove
- Protective coatings can be applied to the wafer surface to shield the die from the slag
- Cost of ownership is prohibitive

Laser Ablation



LASER DICE WAFER ON TAPE AND FILM FRAME

Laser Ablation



Residue from
protective film
and slag after
cleaning

Low-K Singulation

- Laser grooving followed by mechanical dicing is a common method for processing Low-K wafers, however, this requires substantial resources
- Mechanical dicing alone can be used for singulating Low-K wafers by utilizing a step cut with a shallow first pass to trench through the dielectric layer. This has proven to be successful for 28nm technology and greater and is more cost effective compared to laser grooving
- Stealth dicing is another method that is becoming more popular for Low-K processing. The stealth process provides a clean cut to help minimize chipping and delamination

Wafer Singulation

Mechanical

- Flexibility
- Cost effective
- Robust process

SnB

Benefits

- Specialty matl's
- Narrow streets
- Dry process

Stealth

- Narrow streets
- High throughput
- Dry process

Ablation

- Narrow streets
- High throughput
- Specialty matl's

Challenges

- Narrow streets
- Chipping
- Wet process

- Thickness
- Limited flexibility
- Die size

- Thickness
- Cost of ownership
- Power effects

- Cleanliness
- Cost of ownership
- Power effects

Pick and Place

- Pick and place is the process of removing the singulated die from the tape and placing it into an output medium
- The most common mediums are waffle packs, gel packs, tape and reel, and tape and frame (known good wafers)
- Picking can be done manually, using tweezers or vacuum wands, or on automated equipment
- Edge pick tools can be utilized for die with sensitive and non-contact surfaces

Inspection

- Inspection identifies all fab and process related defects on the wafer or in die form
- Inspection is performed either manually or using automated equipment
- Visual inspections can occur at any point during the die prep flow, but are typically done after singulation and pick
- Multiple inspections can be used to identify and track process induced defects